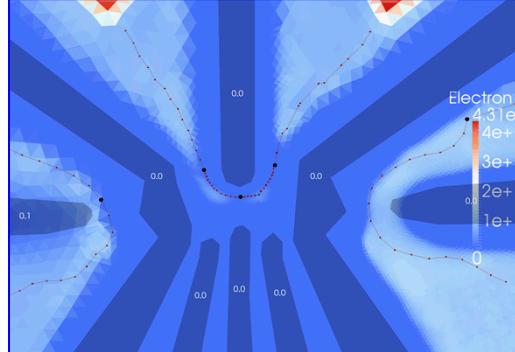
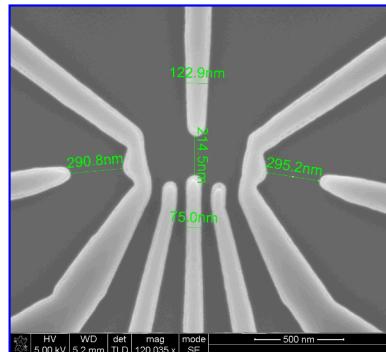
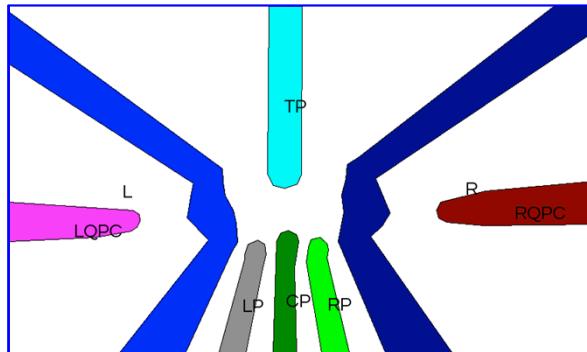


*Exceptional service in the national interest*



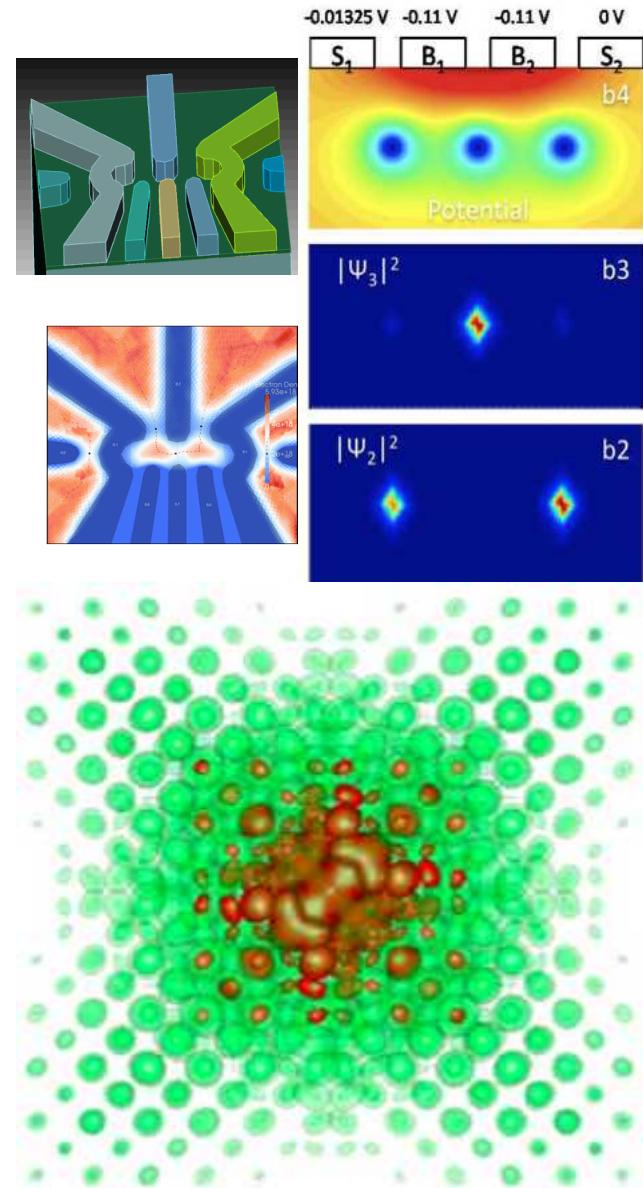
# Modeling Silicon Qubits

## Richard P. Muller, Sandia National Laboratories

## Quantum Materials Workshop, October 2014

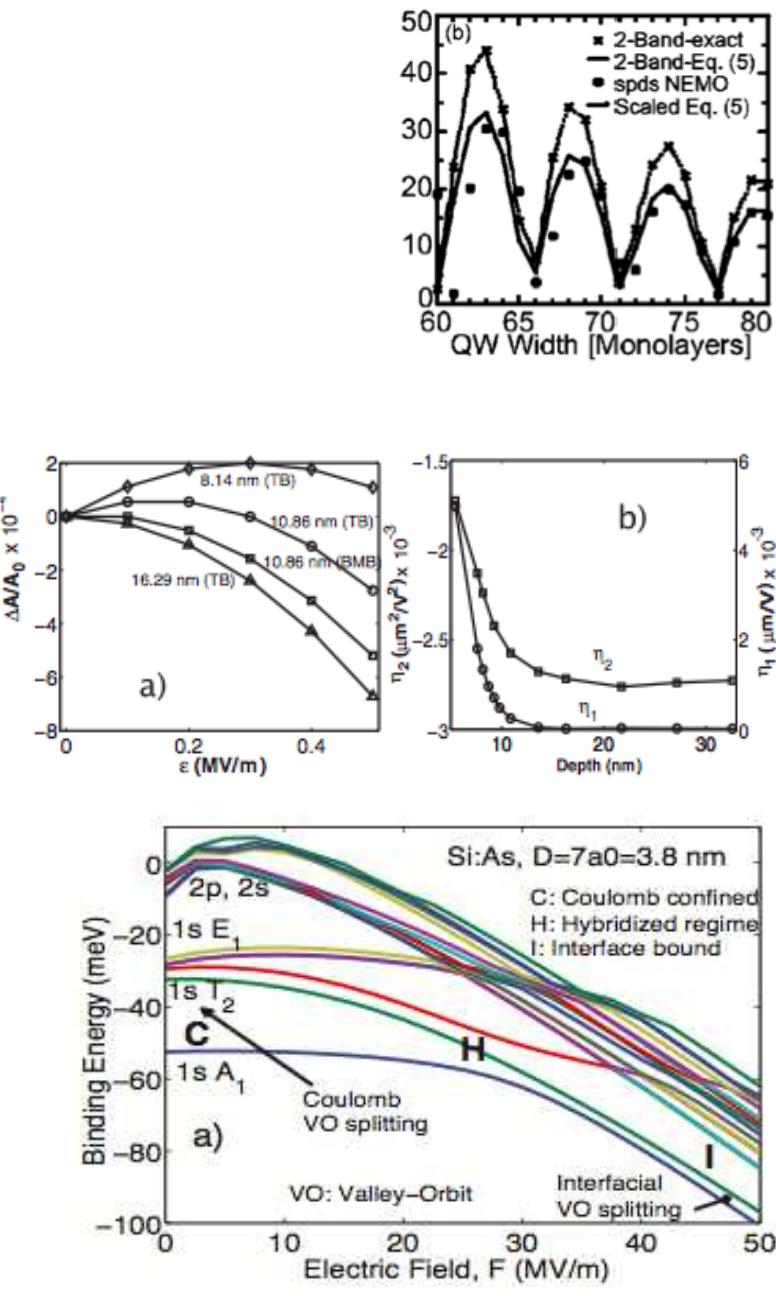
# Why is simulating Si qubits hard?

- Size of relevant systems requires huge calculations
- Quantum dots:
  - $100 \times 20 \times 2 \text{ nm} \sim 250,000 \text{ atoms}$
  - Need far more atoms for:
    - Oxide
      - And don't understand disorder
    - Gates/ground plane
- Donors
  - Si:P donor 2-4 nm Bohr radius
  - Devices typically at least  $60 \times 30 \times 30 \text{ nm}$ 
    - 1.6 M atoms
- DFT is looking promising:
  - LW Wang (2009): Si:In 64,000 calculation



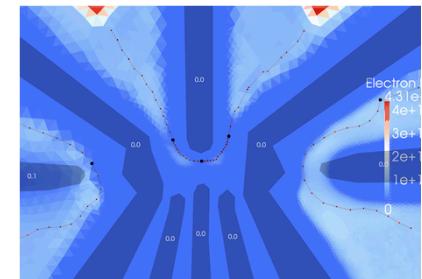
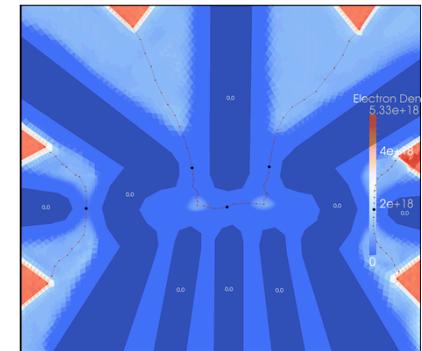
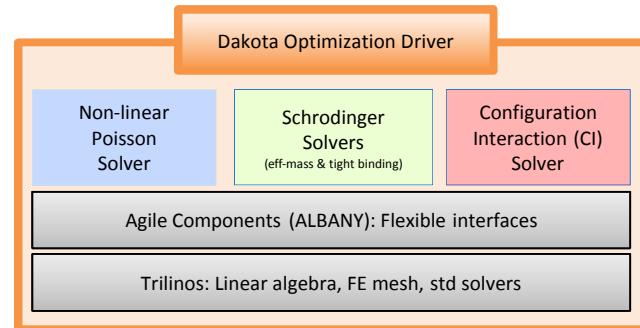
# Tight Binding Methods

- Semiempirical parameterization of electronic structure theory
  - Slater/Koster 1954, basic theory
  - Harrison, very compact and transferrable theory for semiconductors
  - Vogl/Hjalmarson/Dow, 1983,  $sp^3s^*$  calculations for VB & CB
  - Boykin/Klimeck/Eriksson... 2004, VS as QW width
- NEMO3D, Klimeck:
  - Robust program for high-precision TB calculations for *huge* systems
  - Rahman 2007 Si:P hfine & Stark control
  - Rahman 2009 Si:P donor & interface states



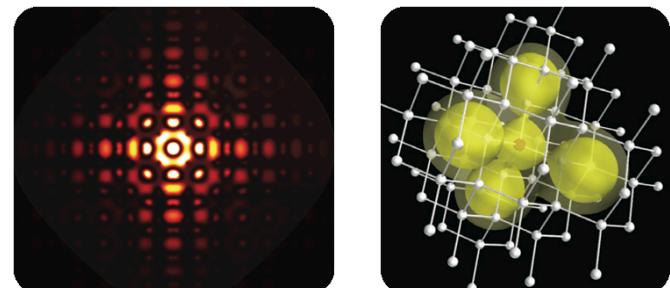
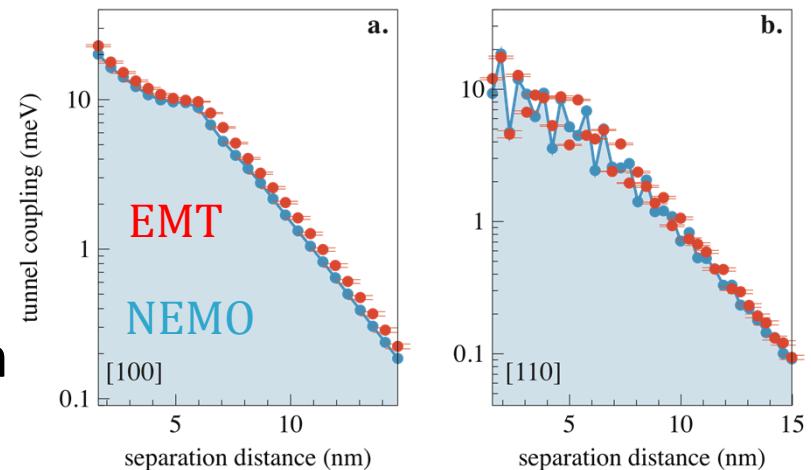
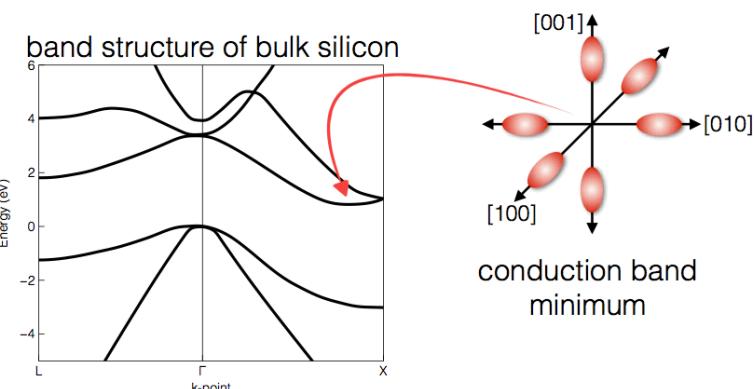
# QCAD

- Gao et al. (2013)
- Few-electron, low-T regime is not covered well using existing device modeling tool
- Develop FEM code using SNL/LDRD funding, with some open, parallel tools
- Semiclassical, Schrodinger-Poisson, and Configuration Interaction solvers
- Broad optimization capabilities
- Interface to NEMO3D



# Multivalley EMT

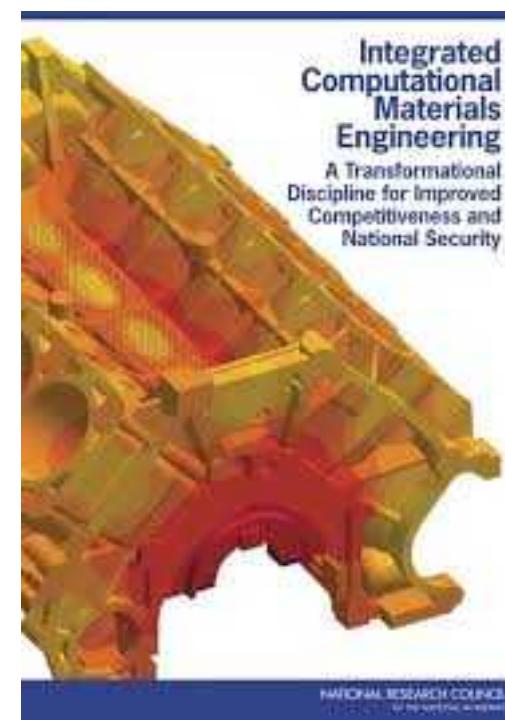
- Seminal work by Kohn/Luttinger, 1955
  - Hfine levels for Group 5 elements
  - $$F = \sqrt{\frac{a^2 b}{\pi}} \exp\{-\sqrt{a^2 \rho^2 + b^2 z^2}\}$$
  - Single-valley, qualitative agreement
- Lot of improvements since then
  - Koiller et al, 2004, Better Bloch functions
  - Ning/Sah, 1971, Central cell correction
- Recent work (Gamble, 2014) combines multivalley EMT, with much more accurate central cell and Bloch functions
  - Near qualitative agreement with tight-binding calculations at a substantially reduced cost, allowing, e.g. millions of scans of tunnel coupling configurations



# How can we make a big difference?



- We need to bring modeling to the point where we can actually do design iterations on a computer rather than in the fab?
- ICME is a good start
  - NRC Report, 2008
  - Appreciates the huge amount of process variation involved in metallurgy and solid mechanics
- We need substantially more sophisticated models for disorder, defects and noise and myriad knobs to tune this with based on empirical data
- We need a huge amount of statistical data so that we can correlate process settings to defect and disorder settings



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